

PATENT ABSTRACTS OF JAPAN

(11)Publication number:

2002-030249

(43)Date of publication of application: 31.01.2002

(51)Int.CI.

C09D183/04 C09D183/08 H01L 21/312

(21)Application number: 2000-214438

(71)Applicant: CATALYSTS & CHEM IND CO LTD

(22)Date of filing: 14.07.2000 (72)Inventor: EGAMI YOSHINORI

> **NAKAJIMA AKIRA KOMATSU MICHIO**

(54) SILICA COATING LIQUID FOR FORMING LOW DIELECTRIC CONSTANT AND SILICA COAT SUBSTRATE WITH LOW DIELECTRIC CONSTANT

PROBLEM TO BE SOLVED: To provide a silica coating liquid for forming low-dielectric constant with a dielectric constant as small as ≤2.5, having low moisture absorbability and high mechanical strength. SOLUTION: This coating liquid contains (A) at least one silicon compound selected from the group consisting of alkoxysilanes of the general formula (I): XnSi(OR)4-n and silane halides of the general formula (II): XnSiX'4-n and (B) an organic template material of the general formula (III): [R1R2R3R4N]+Y- (in these formulas, X is H, F, a 1-8C alkyl, fluorine-substituted alkyl, aryl or vinyl; R is H, a 1-8C alkyl, aryl or vinyl; X' is a halogen atom; n is an integer of 0-3; R1 is a 1-20C hydrocarbon group; R2 to R4 are each H or a 1-20C hydrocarbon group and may be the same as R1; and Y is a halogen atom or OH).

LEGAL STATUS

[Date of request for examination]

29.07.2004

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]

Copyright (C); 1998,2003 Japan Patent Office